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### AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application.

Claims 1-6 (Cancelled)

7. (Currently Amended) [[The compound of claim 5,]] A compound comprising:  
a polymeric chain;

a dissolution inhibitor group attached to the polymeric chain at an anhydride linkage,  
wherein the anhydride linkage comprises sulfur, and wherein the anhydride linkage  
comprises a sulfinic acyl group.

8. (Currently Amended) [[The compound of claim 5,]] A compound comprising:  
a polymeric chain;

a dissolution inhibitor group attached to the polymeric chain at an anhydride linkage,  
wherein the anhydride linkage comprises sulfur, and wherein the anhydride linkage  
comprises two acyl groups bonded to a sulfur atom.

9. (Currently Amended) [[The compound of claim 1,]] A compound comprising:  
a polymeric chain; and

a dissolution inhibitor group attached to the polymeric chain at an anhydride linkage,  
wherein the anhydride linkage comprises phosphorous.

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10. (Original) The compound of claim 9, wherein the anhydride linkage comprises a phosphoryl acyl group.
11. (Currently Amended) The compound of claim [[1]] 7, wherein the dissolution inhibitor group comprises an alicyclic group.
12. (Original) The compound of claim 11, wherein the alicyclic group comprises a ring selected from an alkylated monocyclic ring and an alkylated polycyclic ring.
13. (Original) The compound of claim 12, wherein the alicyclic group comprises a group selected from methyl cyclopentyl, methyl cyclohexyl, methyl adamantyl, and norbornyl.
14. (Currently Amended) A composition comprising:  
  
the compound of claim [[1]] 7; and  
  
a radiation sensitive acid generator capable of generating an acid if exposed to radiation.
15. (Original) A method comprising:  
  
forming a layer of the composition of claim 14 over a substrate;  
  
exposing the layer to patterned radiation;  
  
heating the exposed layer; and  
  
developing the exposed layer.
16. (Previously Presented) A compound comprising:  
  
a polymeric chain including polyhydroxystyrene;

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a dissolution inhibitor attached to the polyhydroxystyrene of the polymeric chain at an anhydride linkage.

17. (Original) The compound of claim 16, wherein the anhydride linkage comprises two acyl groups bonded to an oxygen atom, wherein a first of the two acyl groups is attached to the polymeric chain, and wherein a second of the two acyl groups is attached to the dissolution inhibitor.

18. (Original) The compound of claim 16, wherein the anhydride linkage comprises sulfur.

19. (Original) The compound of claim 16, wherein the anhydride linkage comprises phosphorous.

20. (Original) A composition comprising on a solvent-dry basis:

from 80 to 99.9 weight percent of the compound of claim 16; and

from 0.1 to 20 weight percent of a photoacid generator.

Claims 21-30 (Cancelled)

31. (Previously Presented) A method comprising:

forming a layer of the composition of claim 20 over a substrate;

exposing the layer to patterned radiation;

heating the exposed layer; and

developing the exposed layer.